REMARKS

Reconsideration and allowance in view of the foregoing amendments and the following remarks are respectfully requested. Applicant submits that the amendments have been made to clearly define the invention and do not raise significant new issues or require additional searching by the Examiner.

Claims 4, 7 and 9 have been amended. Claims 3-4 and 7-16 are pending in this application.

Claim Rejections – 35 U.S.C. §102

1. Claims 7-8 stand rejected under 35 U.S.C. §102(e) as being anticipated by Park et al. (US Patent 6,753,252). Applicant traverses the rejection for the following reasons.

Park et al. at least fails to disclose the step of removing the conductive material and the insulating film spacers at a removable region such that the conductive material remains on the first contact plug to form a second contact plug and the insulating film spacers only remain at both sides of the second contact plug, as recited in claim 7, as amended. This feature is illustrated in Figs. 6A-6B of the present invention. As shown in the figures, the conductive material and the insulating film spacers formed at an isolation region are removed, whereas the second contact plug 78 and the insulating film spacer 77 remain in the junction region. In contrast, according to Park et al., the spacers 26 remain both in array area 30 and the support area 32 as shown in Fig. 8 of Park et al.

In the Office Action at page 3, the Examiner has merely stated a part of the removing step of the claimed invention and failed to make a specific reference to the portion of the Park reference which describe the step of removing the insulating film spacers at a removal region. The Examiner is respectfully requested to point out the specific drawing or passages which describe the above feature of the claimed invention.

Therefore, Applicant respectfully submits that claim 7 and its dependent claim 8 are not anticipated by Park et al. under 35 U.S.C. §102(e).

2. Claims 3-4 and 7-16 stand rejected under 35 U.S.C. §102(e) as being anticipated by Park et al. (US Patent 6,387,759). Applicant traverses the rejection for the following reasons.

Park et al. also fails to disclose the step of removing the conductive material and the insulating film spacers in the isolation region, as recited in claim 3, the step of removing the conductive material and the insulating fiber spacers at a removal region, as recited in amended claim 7 and the step of removing the second conductive material and the second spacers on the first interlayer dielectric film, as recited in amended claim 9. In the Office Action, the Examiner pointed out Figures 7C-7D which describe the above features of the claimed invention. Contrary to the Examiner's assertion, all of the gates include sidewall spacers 212 in the drawings. Figures 9A-9E also show the sidewall spacers remain in the cell region CA2 and the double layered sidewall spacers 232 in the peripheral region. In this regard, Applicant submits that Park et al. is still deficient in describing the step of removing the insulating film spacers in the isolation region, as recited in claim 3, the step of removing the conductive material and the insulating fiber spacers at a removal region, as recited in amended claim 7, and the step of removing the second spacers on the first interlayer dielectric film, as recited in amended claim 9.

Therefore, it is submitted that independent claims 3, 7 and 9 and their dependent claims 4, 8 and 10-16 are not anticipated by Park et al. under 35 U.S.C. §102(e).

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Conclusion

The prior art made of record and not relied upon is noted.

All objections and rejections having been addressed, it is respectfully submitted that claims 3-4 and 7-16 are now in condition for allowance and a notice to that effect is earnestly solicited. If any issues remain to be resolved, the Examiner is cordially invited to telephone the undersigned attorney at the number listed below.

Respectfully submitted,

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